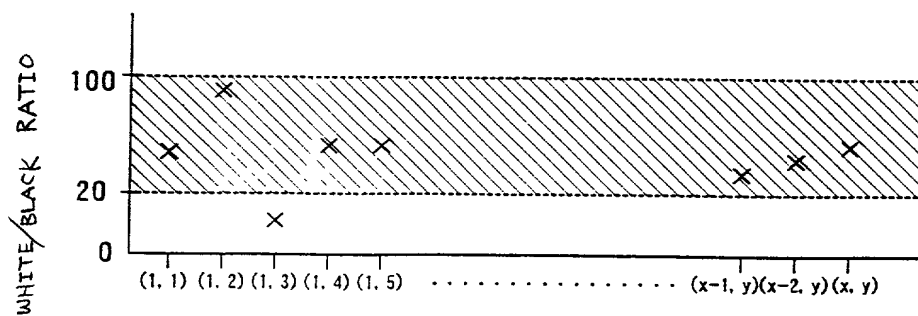


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Fig. 3(A)

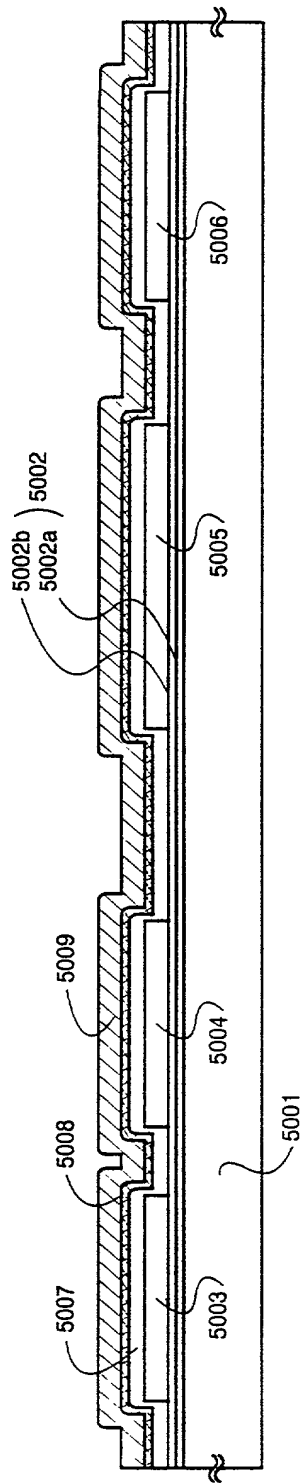
$(1, 1)$	$(2, 1)$	$(3, 1)$	$(4, 1)$		$(x-1, 1)$	$(x, 1)$
$(1, 2)$	$(2, 2)$	$(3, 2)$	$(4, 2)$		$(x-1, 2)$	$(x, 2)$
$(1, 3)$	$(2, 3)$	$(3, 3)$	$(4, 3)$		$(x-1, 3)$	$(x, 3)$
$(1, 4)$	$(2, 4)$	$(3, 4)$	$(4, 4)$		$(x-1, 4)$	$(x, 4)$
$(1, y-1)$	$(2, y-1)$	$(3, y-1)$	$(4, y-1)$		$(x-1, y-1)$	$(x, y-1)$
$(1, y)$	$(2, y)$	$(3, y)$	$(4, y)$		$(x-1, y)$	(x, y)

Fig. 3(B)



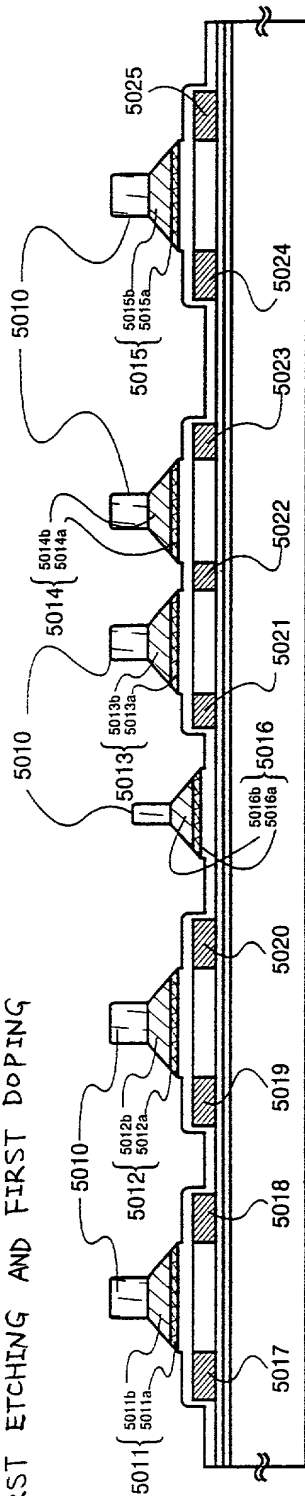
FORMATION OF ISLAND SEMICONDUCTOR LAYER, GATE-INSULATING FILM,
AND FIRST AND SECOND CONDUCTING FILMS FOR GATE ELECTRODES

Fig. 4(A)



FIRST ETCHING AND FIRST DOPING

Fig. 4(B)



SECOND ETCHING

Fig. 4(C)

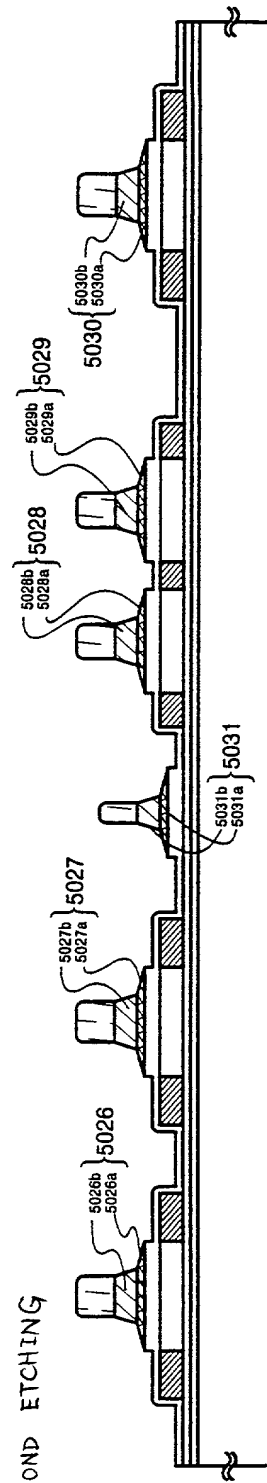


Fig. 5(A) SECOND DOPING

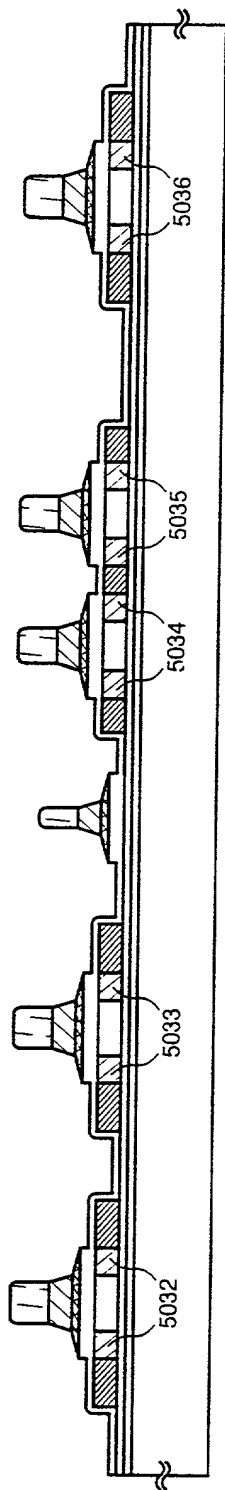


Fig. 5(B) THIRD ETCHING

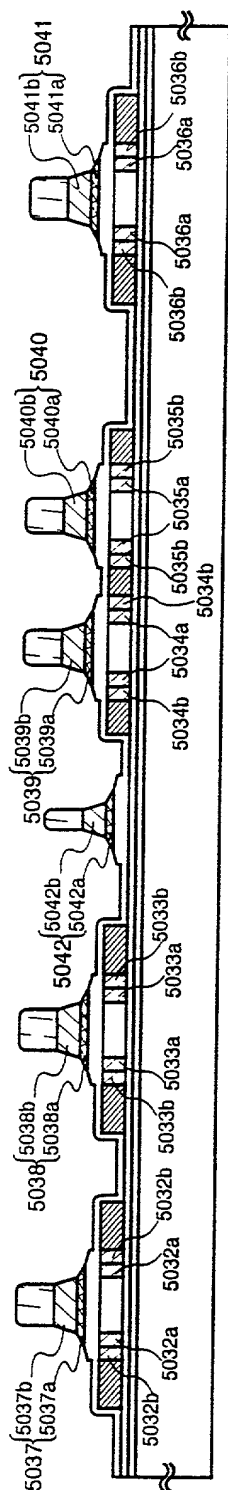
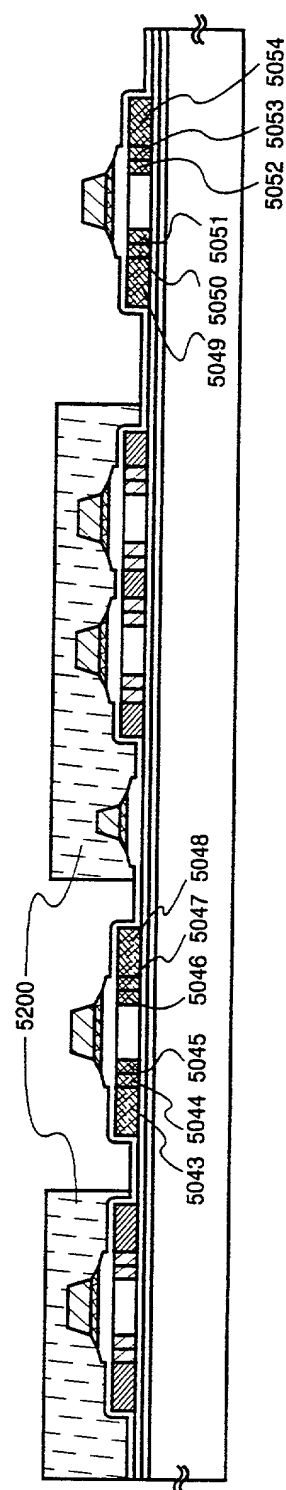
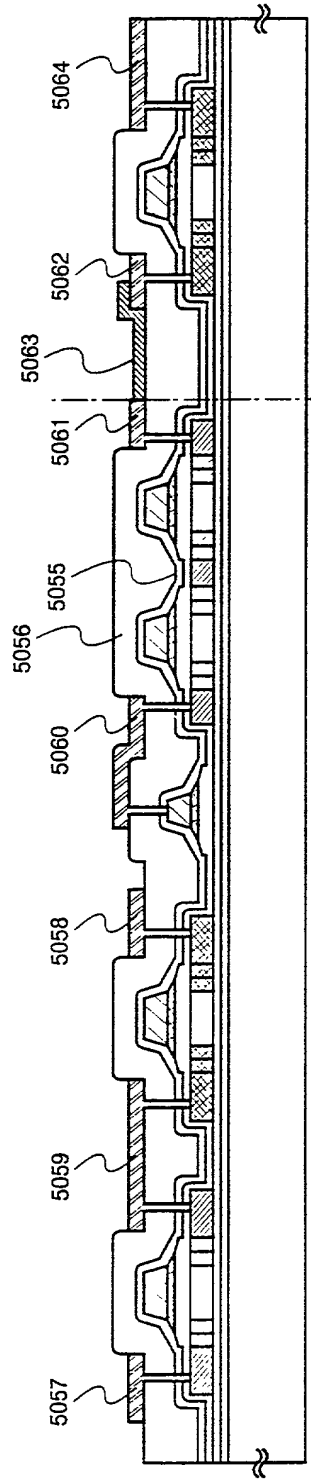


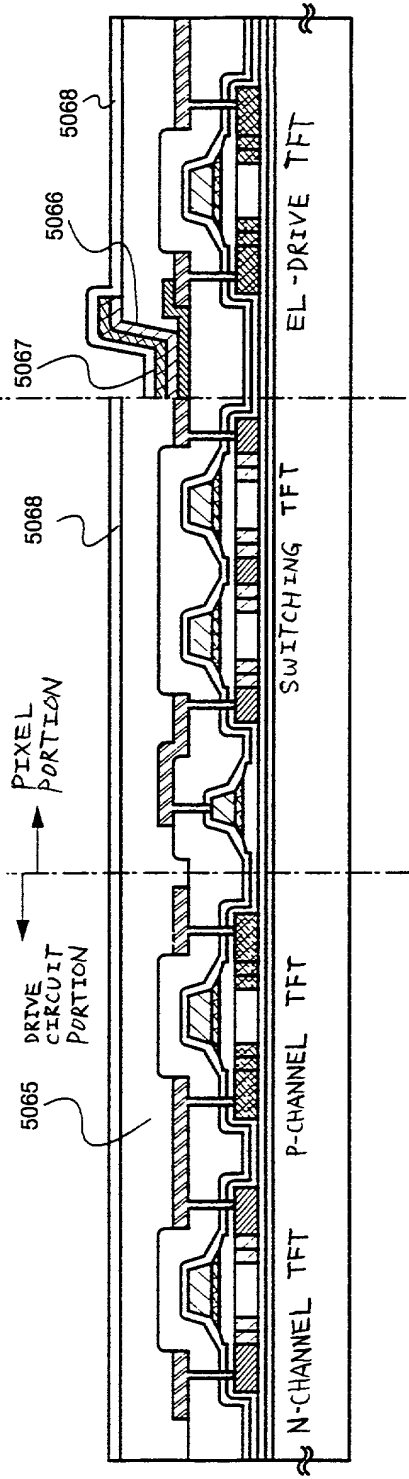
Fig. 5(c) THIRD DOPING

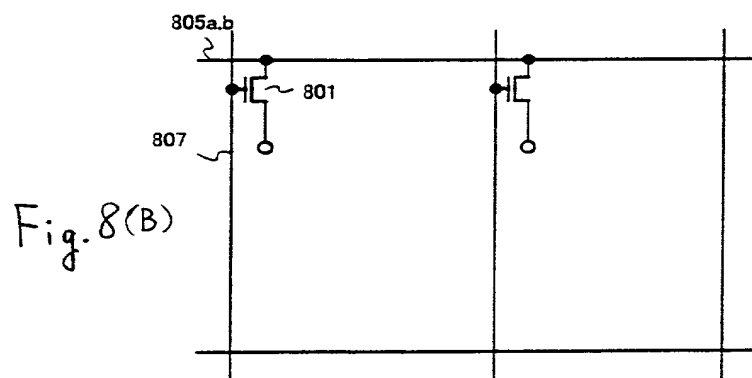
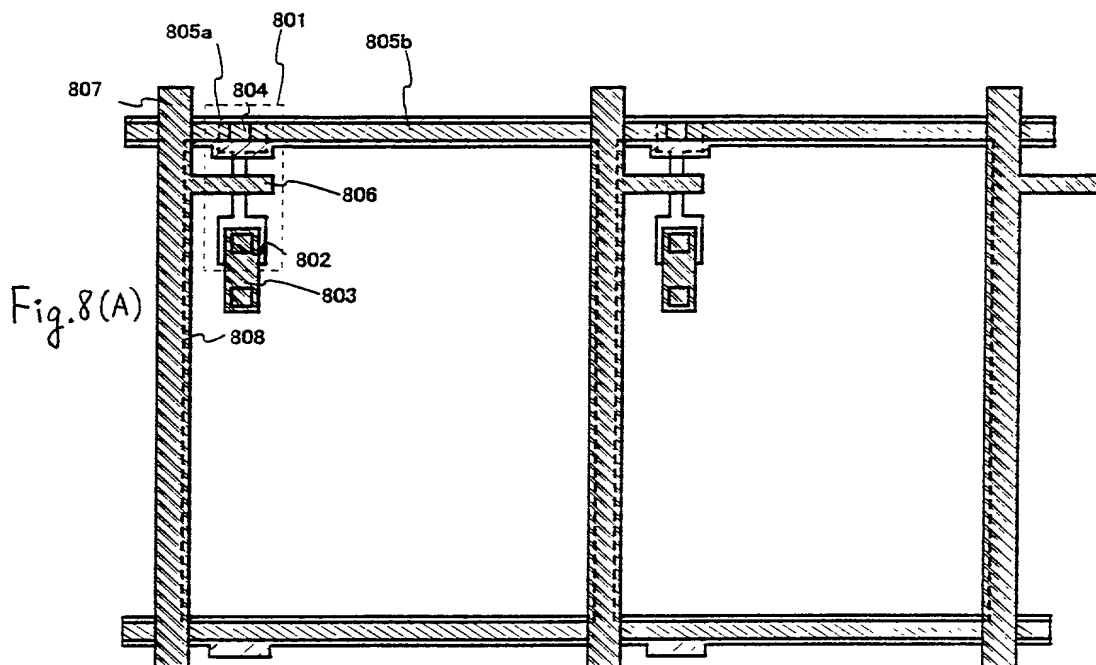


FORMATION OF THE FIRST AND SECOND INTERLAYER - INSULATING FILMS,
Fig. 6(A) WIRINGS AND PIXEL ELECTRODES



FORMATION OF THE THIRD INTERLAYER - INSULATING FILM, EL LAYER,
Fig. 6(B) CATHODES AND PASSIVATION FILM





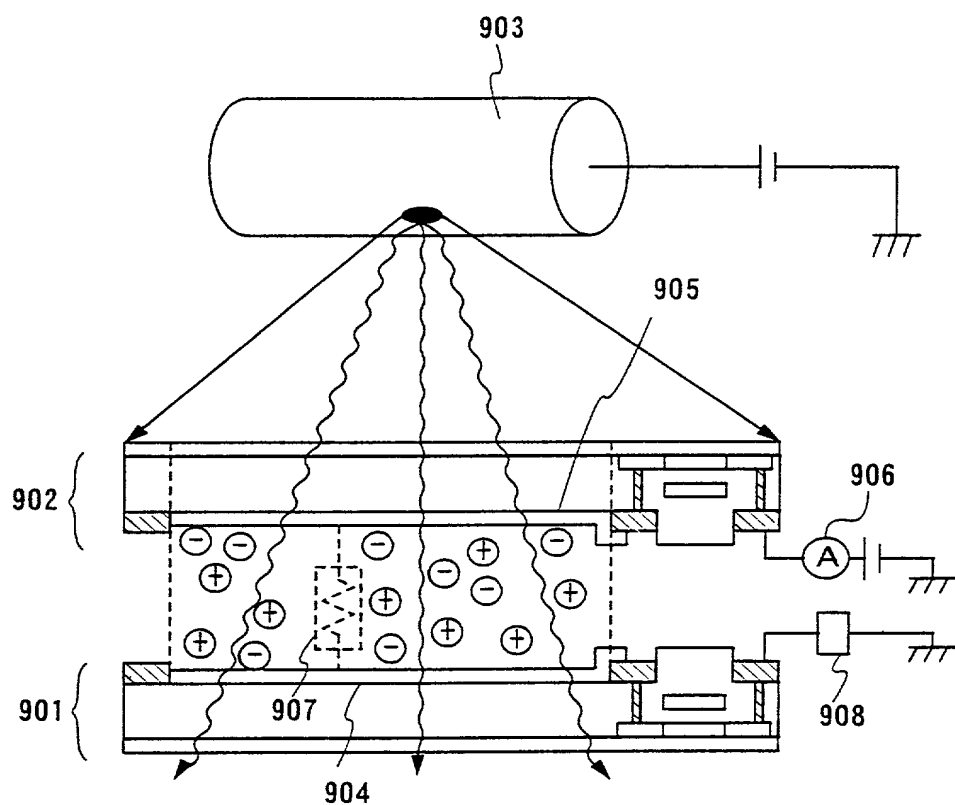


Fig. 9

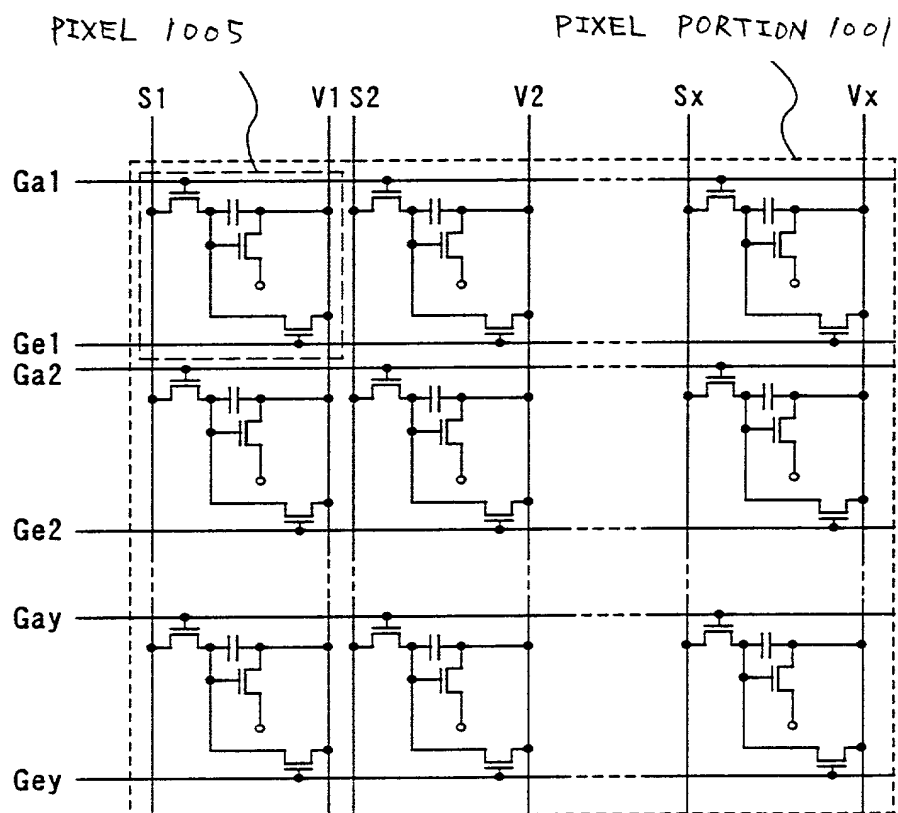


Fig. 10

SOURCE OF ELECTROMAGNETIC
WAVES 1101

POWER SOURCE 1104

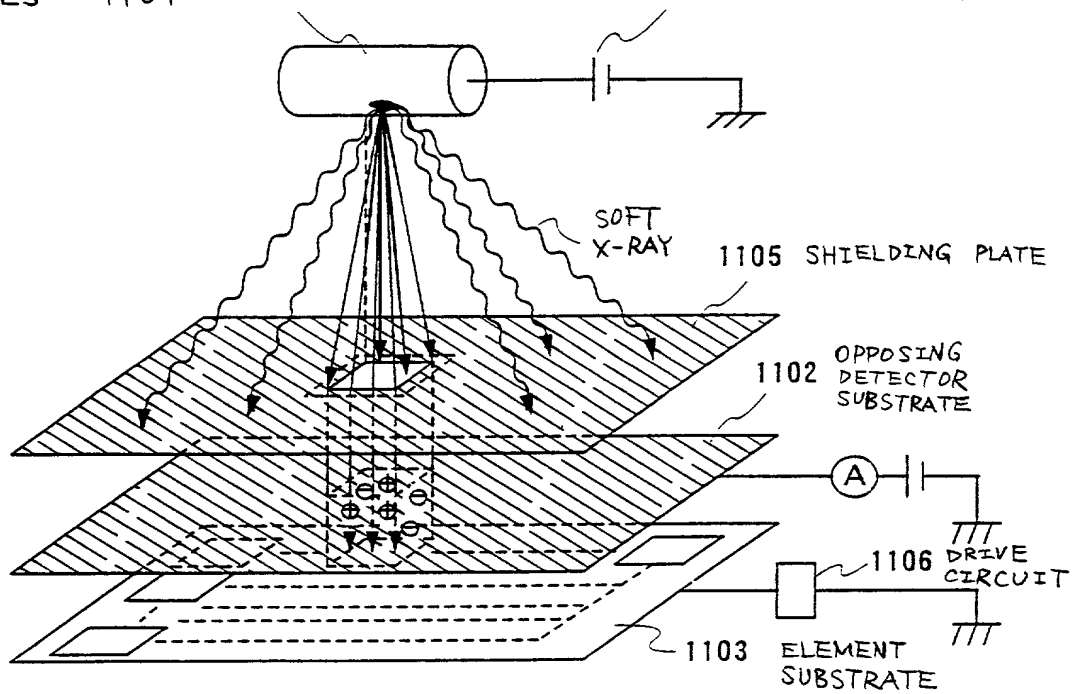


Fig. 11

TOP SECRET

SOURCE OF ELECTROMAGNETIC WAVES

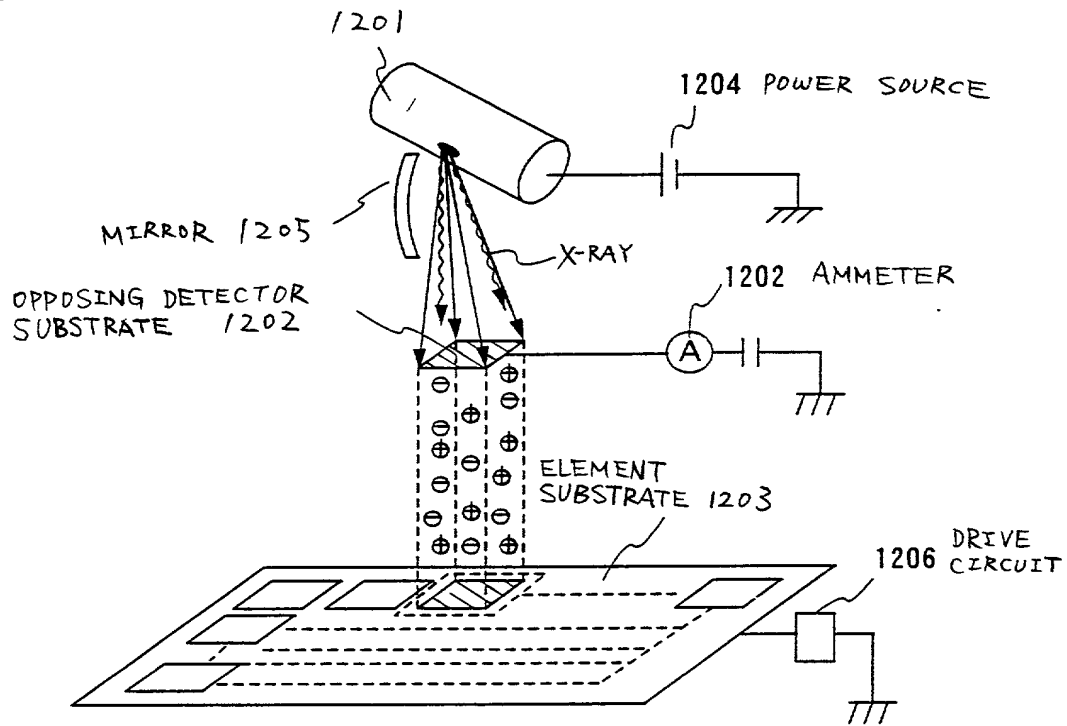
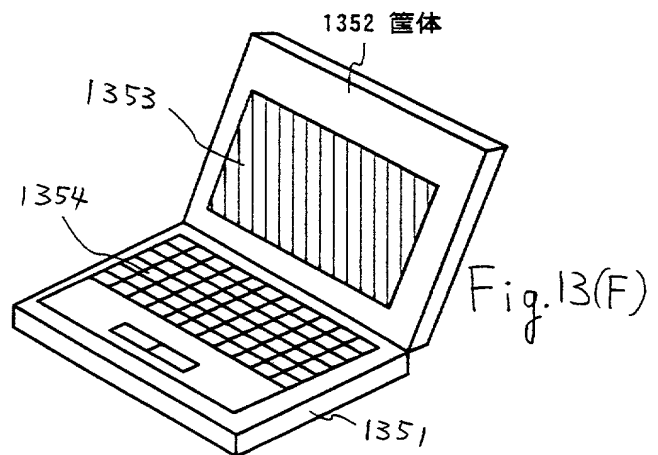
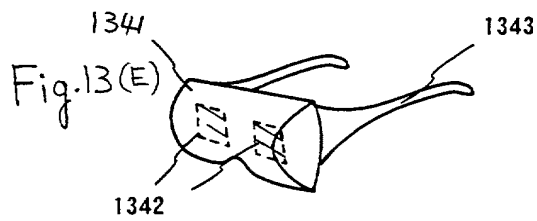
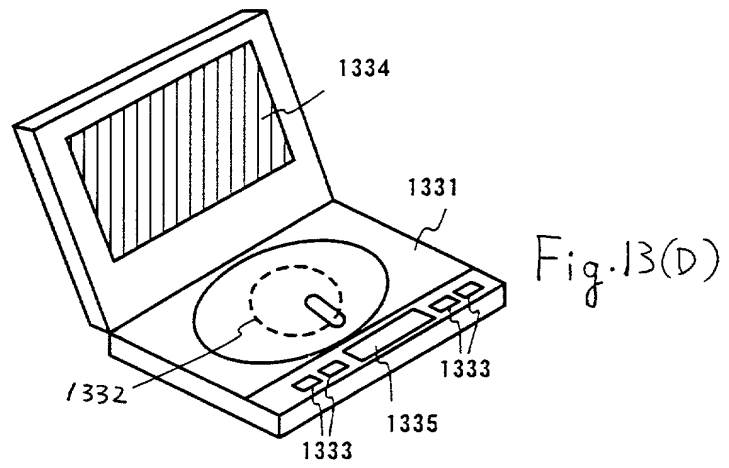
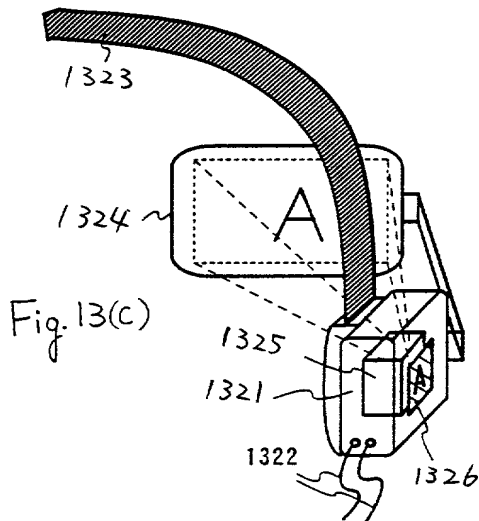
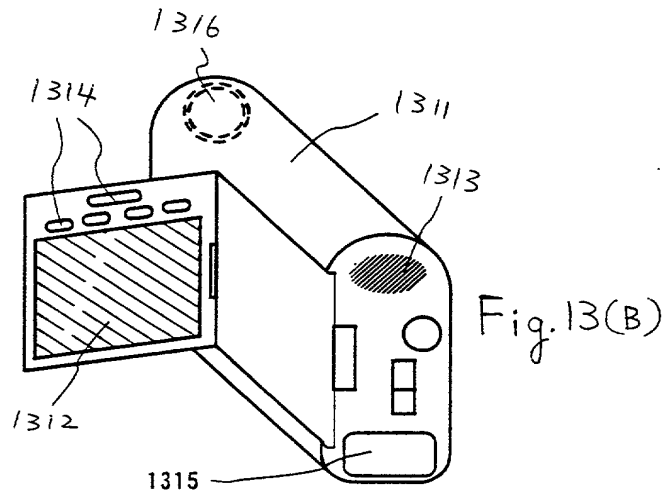
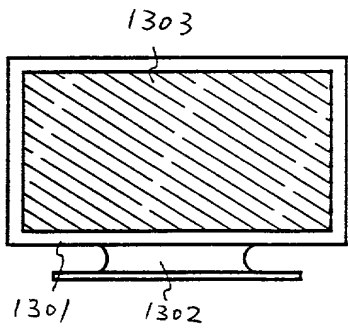


Fig. 12

Fig. 13(A)



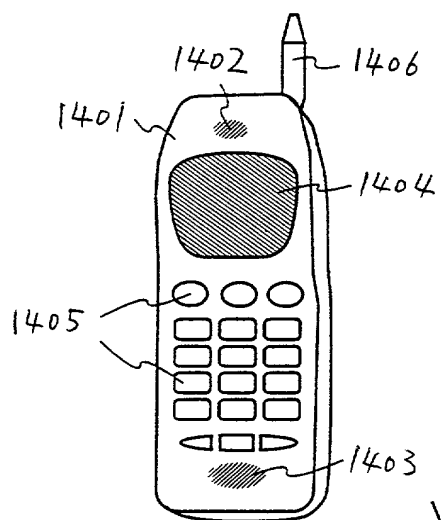


Fig. 14(A)

Fig. 14(B)

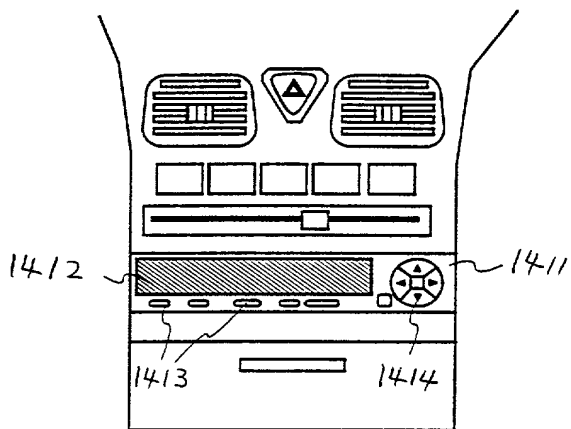


Fig. 14(c)

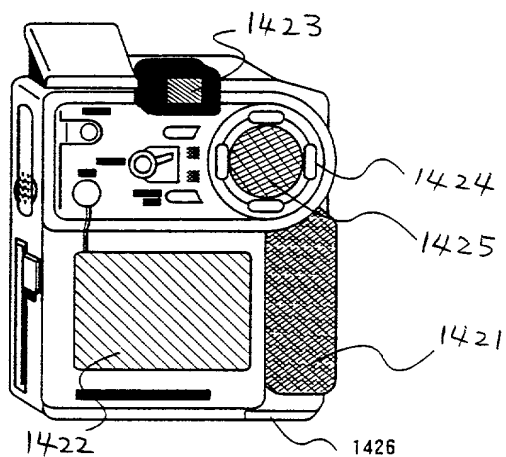


Fig. 15

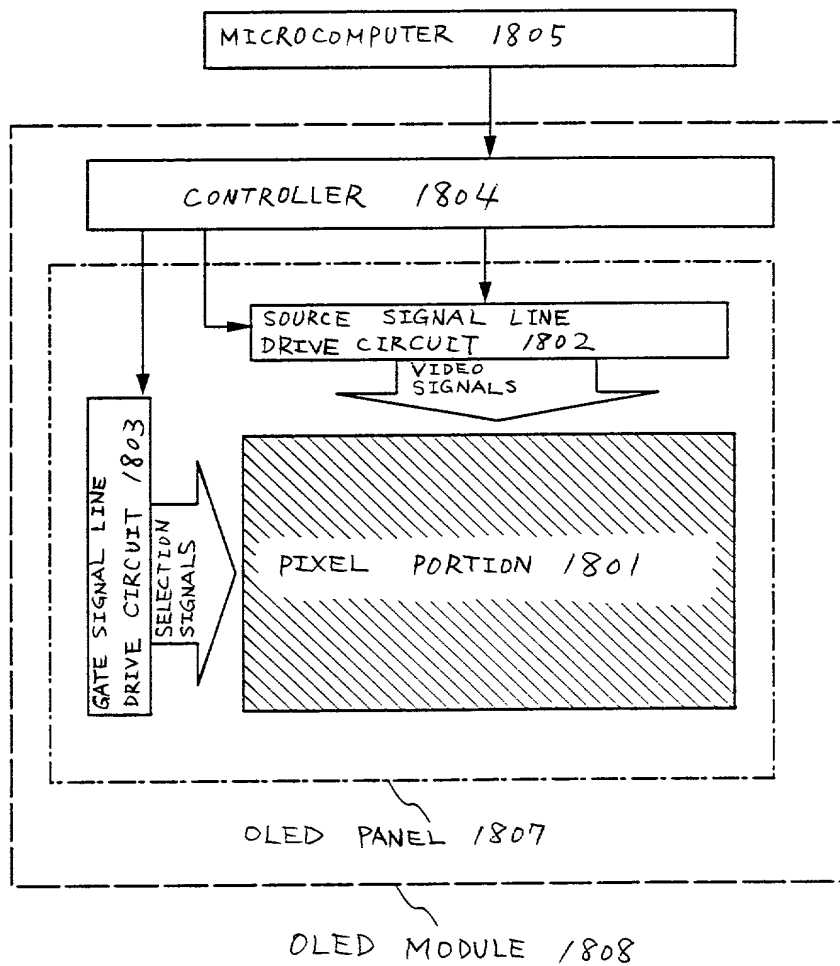


Fig. 16(A)

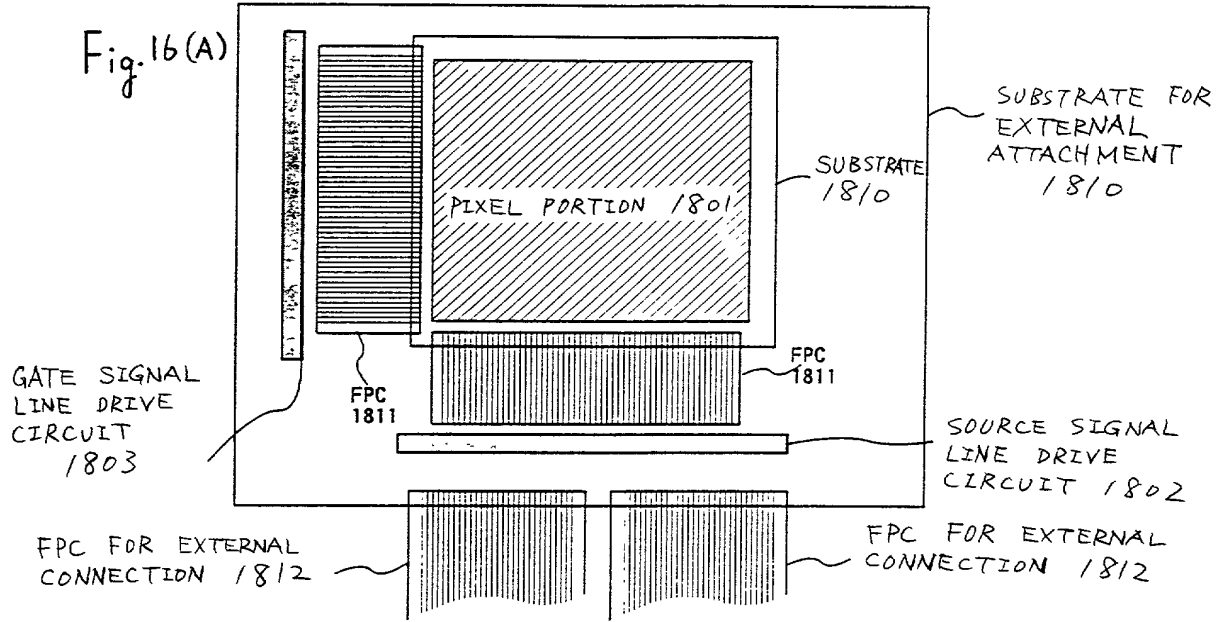


Fig. 16(B)

